ANOMALOUS THERMOELECTRIC POWER OF FeCr₂S₄ NEAR THE CURIE TEMPERATURE

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An anomalous increase of the thermoelectric power in semiconducting, p-type FeCr₂S₄ is found near the Curie temperature. Analysis of the Fermi energy indicates that this effect is apparently due to an additional kinetic energy which the charge carriers acquire through magnon-hole interaction.

In a recent paper by Wasscher and Haas¹ the anomalous increase of the thermoelectric power, α , in semiconducting MnTe below its Néel temperature² is attributed to magnon drag.³ This effect arises from a strong interaction between spin waves (magnons) and charge carriers through which additional carriers are dragged along a temperature gradient, thereby increasing α above the normal diffusion term. In order to fit the experimental data for MnTe to the magnon-drag model, a very short magnon-carrier relaxation time of ~10⁻¹⁵ sec had to be assumed.¹

We wish to report in this Letter an anomalous thermoelectric power increase, similar to the one found in MnTe, which we observed in single crystals of $FeCr_2S_4$. $FeCr_2S_4$ is known to be a semiconducting, normal spinel which becomes ferrimagnetic below 195°K.⁴ The results of our measurements agree with the general picture of a *p*-type semiconductor and are shown in Fig. 1. At low temperatures, α increases with temperature *T*, in a way typical for extrinsic semiconductors. Between 160°K and the Curie temperature, α increases anomalously. The decrease of α at high temperatures is due to intrinsic conduction, as will be shown below.

If one calculates α vs T for an extrinsic, nondegenerate semiconductor and matches the curve between 120 and 160°K in Fig. 1, the ther-



FIG. 1. Thermoelectric power α as a function of temperature T for FeCr₂S₄ single crystal.

moelectric power should follow the broken line. The additional thermoelectric power above 160°K, therefore, is likely to be due to the magnetic nature of $FeCr_2S_4$. To analyze our data further, we write the general expression of α for a *p*-type semiconductor,

$$\alpha = (1/eT)(E_{\rm F} + E_{\rm K}), \qquad (1)$$

where e is the electron charge, $E_{\mathbf{F}}$ is the Fermi energy, and E_K is the kinetic energy of the holes. For a broad-band semiconductor it is usually assumed⁵ that E_K is of the order of the thermal energy, kT (where k is Boltzmann's constant). We assume the same to be the case for $FeCr_2S_4$, since Hall measurements indicate band conduction below 200°K (Hall mobilities of the order of $10 \text{ cm}^2/\text{V}$ sec near 110°K). A plot of $\alpha T - kT$ vs T will then give the temperature dependence of the Fermi energy in eV. The results of such a calculation with the data of Fig. 1 are shown in the upper curve of Fig. 2. This curve exhibits two interesting features. At high temperatures, above 400°K, the Fermi energy levels off, indicating intrinsic conduction. This conclusion is further sup-



FIG. 2. Upper part: Fermi energy as function of temperature T calculated from data of Fig. 1. Lower part: Additional kinetic energy ΔE_{K} acquired by holes near Curie temperature T_{C} .

ported by the electrical conductivity which increases in this temperature region exponentially with an activation energy of 0.29 eV.

A second interesting feature of Fig. 2 is a bump in $E_{\mathbf{F}}$ vs T near the Curie temperature. An anomalous increase of $E_{\mathbf{F}}$ at a given temperature could only arise from an increase of the effective mass m^* due to band narrowing in approaching $T_{\mathbf{C}}$. Although such behavior is conceivable,⁶ the $E_{\rm F}$ vs T curve should not show in this case two points of inflection near $T_{\rm C}$, since this would mean that m^* after an initial increase decreases again. We are, therefore, inclined to assume that around $T_{\rm C}$ the curve of $E_{\mathbf{F}}$ vs T is not a true reflection of the behavior of the Fermi level. Instead, we propose that the charge carriers acquire in this temperature region an additional kinetic energy, ΔE_K , due to a magnon-hole interaction. If we calculate the difference between the original curve of Fig. 2 and a smooth curve drawn along the broken line shown in the figure, we obtain this additional kinetic energy as a function of temperature. The result of this calculation is plotted in the lower part of Fig. 2. At the Curie temperature ΔE_K reaches a maximum and falls off rapidly towards

higher and lower temperatures. This behavior is qualitatively consistent with the magnondrag model since the magnon-carrier relaxation time becomes extremely short when approaching $T_{\rm C}$ from lower temperatures.¹ That ΔE_K does not disappear abruptly at $T_{\rm C}$ is an indication of magnetic short-range order up to approximately 230°K.

Although the above analysis shows a qualitative agreement of our data with the magnondrag model, a final proof can only come through a quantitative comparison. For this we need to know the magnon-magnon and magnon-hole relaxation times, which we cannot derive from the present measurements. Further detailed electrical transport measurements are in progress.

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DIRECT OBSERVATION OF LITHIUM-DEFECT INTERACTION IN SILICON BY ELECTRON PARAMAGNETIC RESONANCE MEASUREMENTS^{*}

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Electron paramagnetic resonance measurements have been used to observe directly the interaction of lithium with damage centers produced by electron irradiation in *n*-type, floatzone silicon. The silicon is characterized by low oxygen concentrations, with lithium as the predominant n-type dopant. Low oxygen concentrations might be expected to foster the interaction of lithium with radiation-induced defects on two counts: (1) Since in silicon containing $\sim 10^{18}/\text{cm}^3$ oxygen the shallow lithium donor is really a (Li-O) complex, the absence of oxygen might make the isolated lithium¹ more mobile and/or susceptible to trapping by other imperfections and defects; (2) the absence of oxygen removes the possibility of forming oxygen-vacancy complexes (A centers),² thus increasing further the likelihood of lithium interacting with vacancies.

Float-zone silicon with quoted oxygen concentrations of $(1-2) \times 10^{15}$ /cm³ and a resistivity of 12 Ω cm (*n* type) was diffused with lithium from a Li-Sn alloy at 400°C to a resistivity of 0.3-0.4 Ω cm and a lithium concentration of about 2×10^{16} /cm³. The material was then bombarded by a 1-MeV electron flux of 1×10^{16} / cm² at room temperature. The epr properties of the material were measured at 27°K using a Varian spectrometer operating at 9.1 kMc/ sec. The major result of our preliminary work is the finding of a new lithium damage-center complex with a relatively high introduction rate which has not heretofore been reported.

The epr spectra of Fig. 1 illustrate our ba-